

**METHOD FOR PROVIDING A LIFTOFF PROCESS USING A SINGLE LAYER
RESIST AND CHEMICAL MECHANICAL POLISHING AND SENSOR
FORMED THEREWITH**

5

ABSTRACT

A method for providing a liftoff process using a single layer resist and chemical mechanical polishing and sensor formed therewith are disclosed. Chemical mechanical polishing is combined with liftoff using only a single resist layer to allow the removal of leftover fencing on the side of a lifted resist pattern.